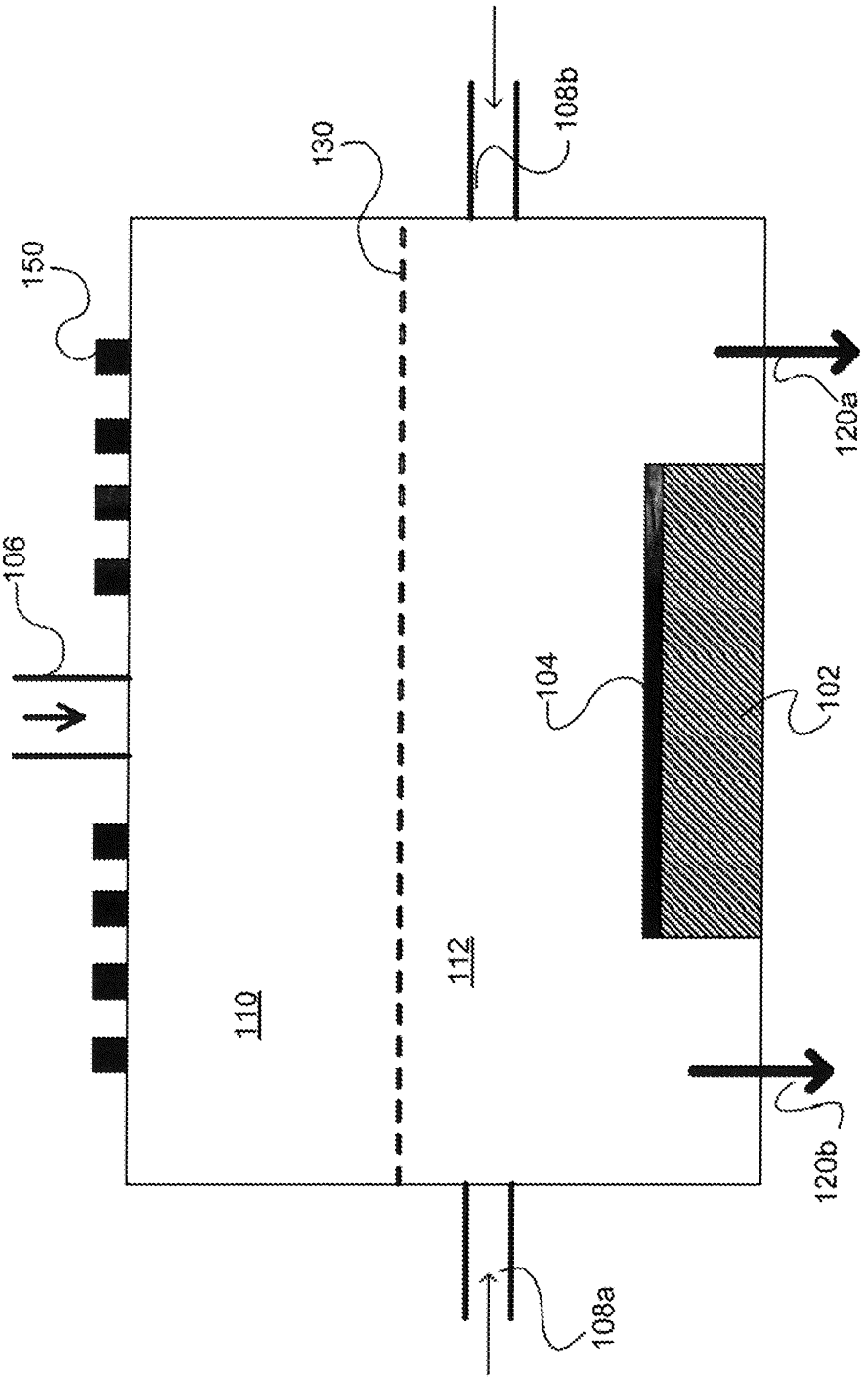


FIG. 1

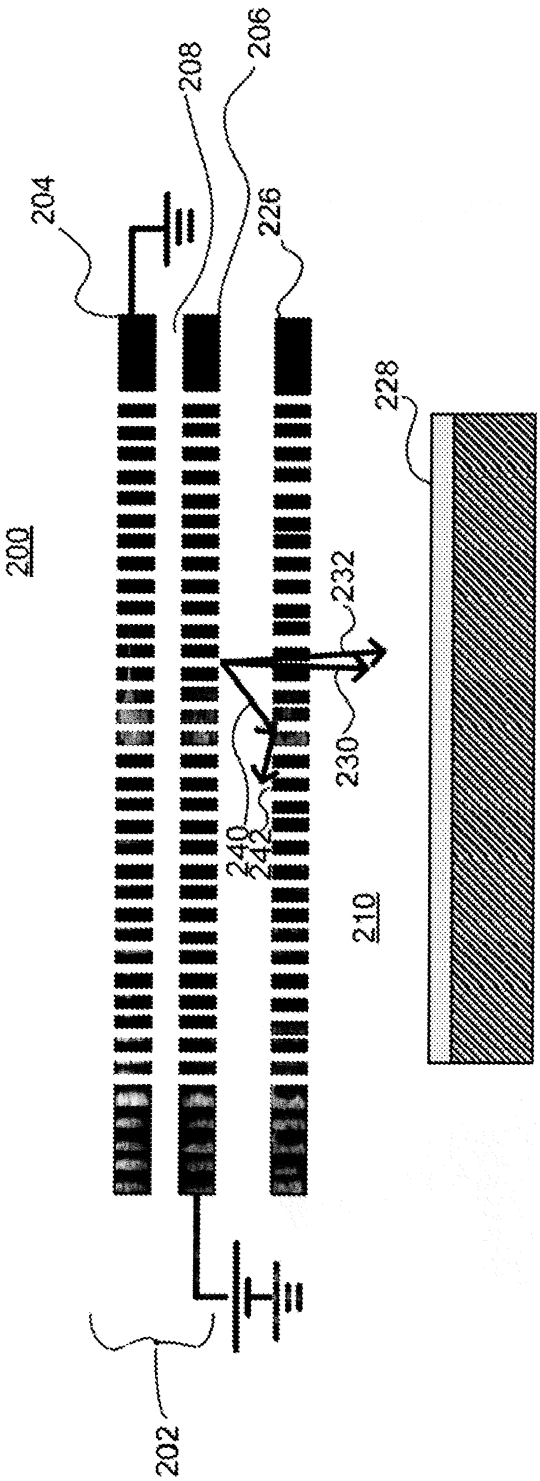


FIG. 2

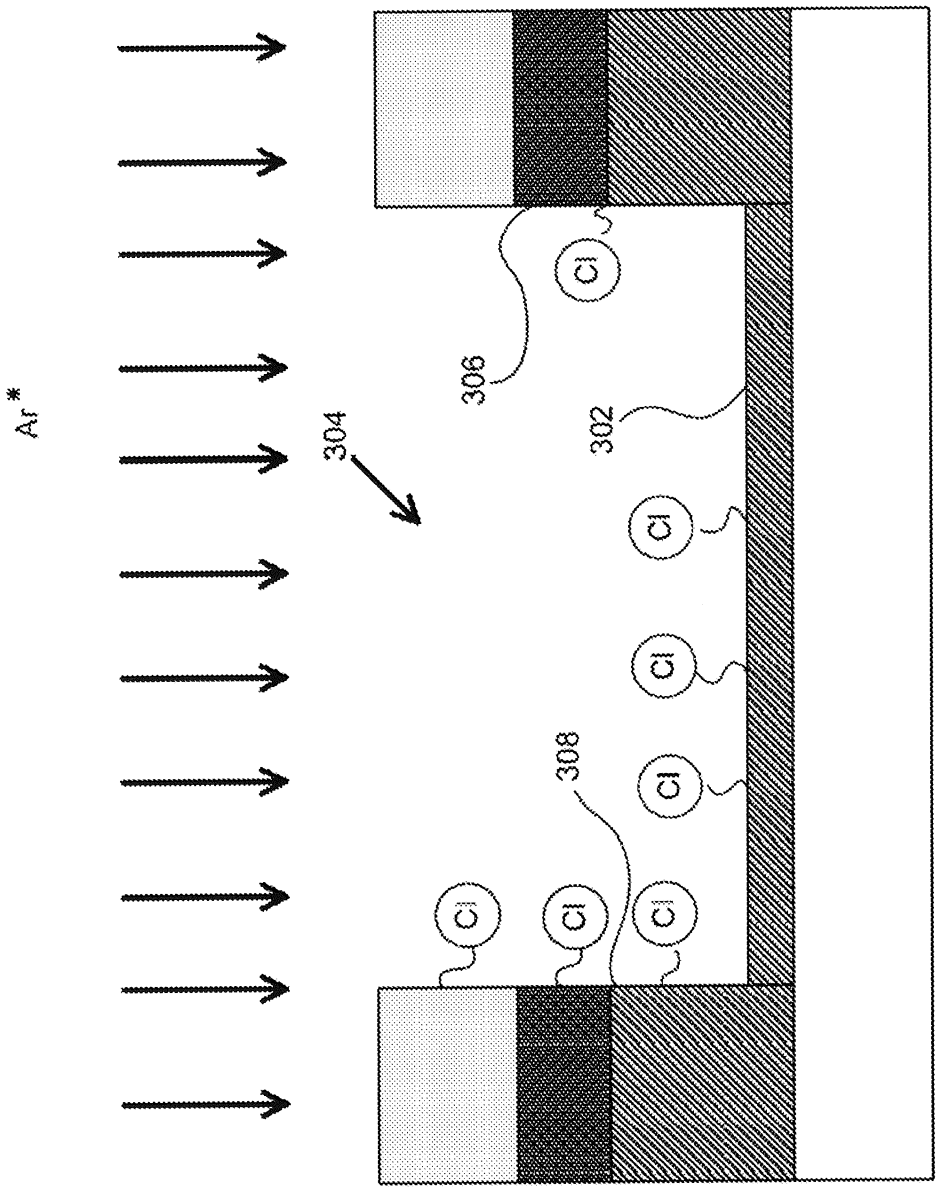


FIG. 3

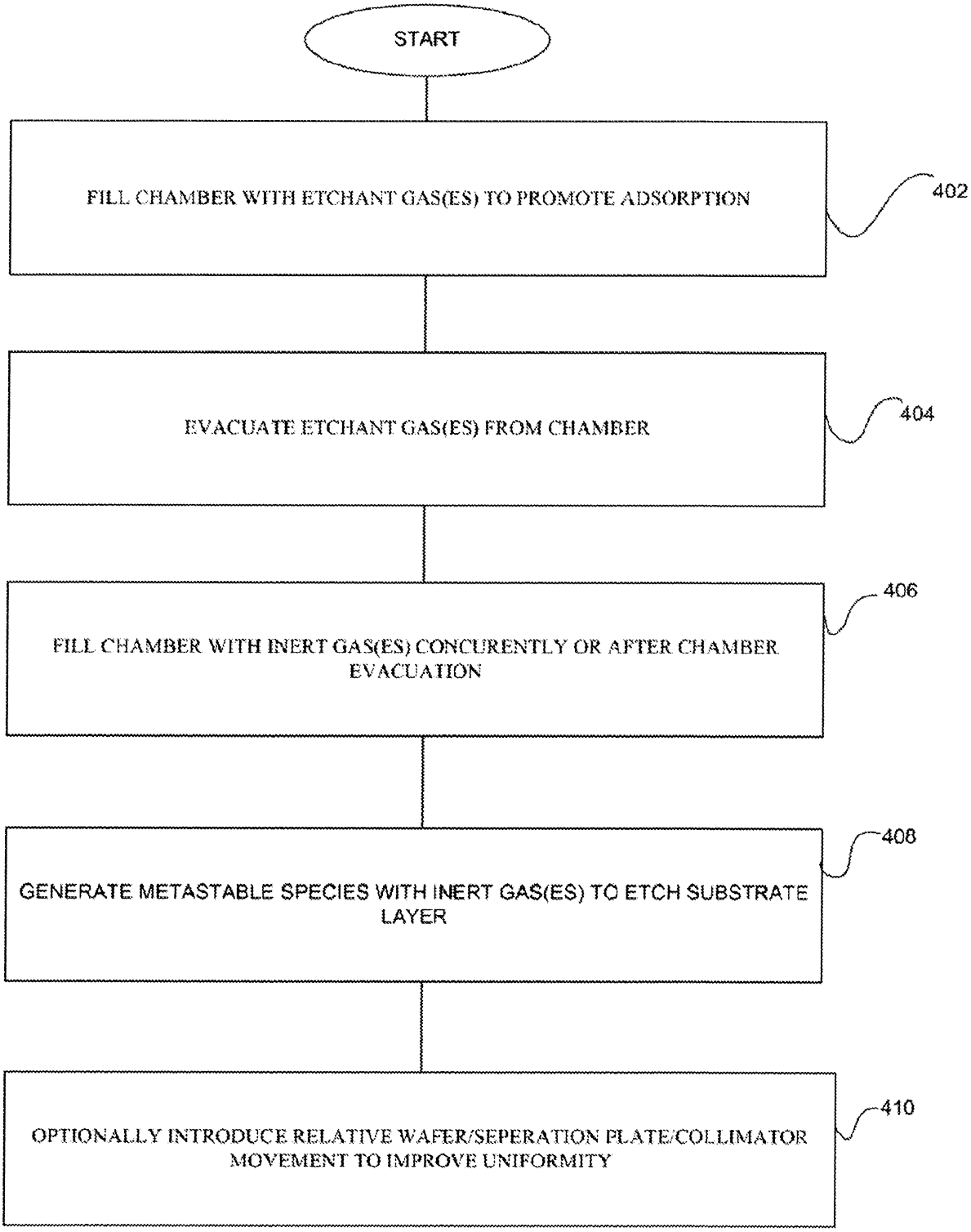

START
FILL CHAMBER WITH ETCHANT GAS(ES) TO PROMOTE ADSORPTION
402
EVACUATE ETCHANT GAS(ES) FROM CHAMBER
404
FILL CHAMBER WITH INERT GAS(ES) CONCURENTLY OR AFTER CHAMBER EVACUATION
406
GENERATE METASTABLE SPECIES WITH INERT GAS(ES) TO ETCH SUBSTRATE LAYER
408
OPTIONALLY INTRODUCE RELATIVE WAFER/SEPERATION PLATE/COLLIMATOR MOVEMENT TO IMPROVE UNIFORMITY
410

FIG. 4